



—● Advanced fiber-to-the-chip solutions ●—

“Low-loss Optical Coupling of PIC with Ultra-compact Fiber-array-units”



Jean-Luc POLLEUX
CTO & co-founder, ICON Photonics
Former Professor, ESIEE Paris,
Univ-Eiffel, ESYCOM-CNRS

About us



Technological independent SME created in **2018**



Offices and Clean Room facilities in France, Paris region



Spinoff of CNRS research center

- **10+ years of R&D** in microfabrication and photonics integrated packaging
- 650m² cleanrooms **production-line** (Class 100) platform
- **Licensing agreement** worldwide with **exclusivity** including 6 patents



8 Headcounts - **Strong R&D** > 50% PhD in Photonics



Develop & commercialize **fiber-to-the-chip connectivity solutions** enabling the next generation of **optical and quantum applications**

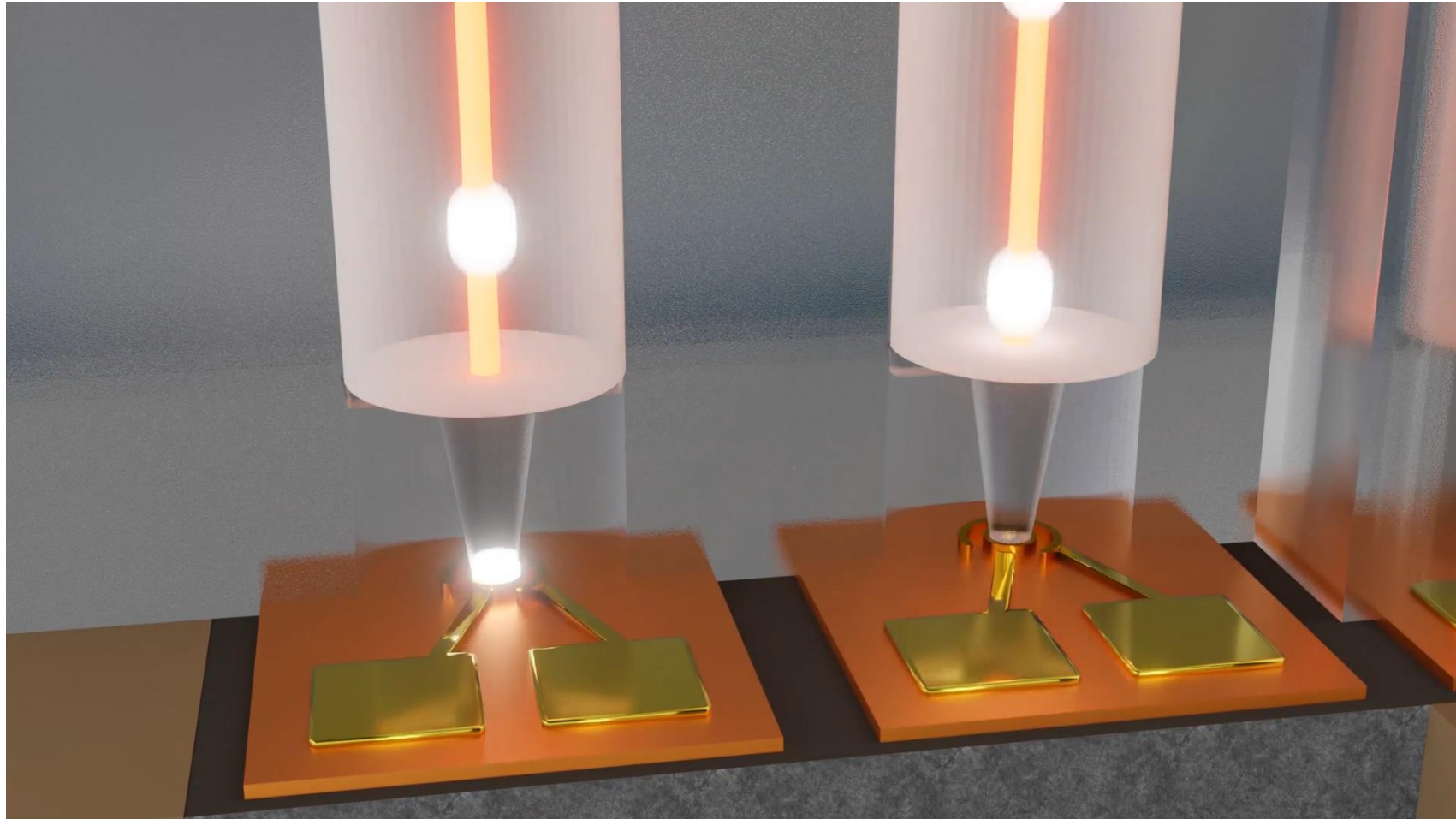
Optical coupling with high-volume production



- Wafer-level Si and Polymer Optical coupling structures
- Wafer level UV lithography
- Wafer bonding
- Through Wafer DRIE

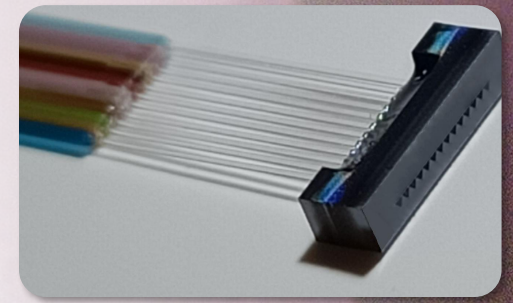
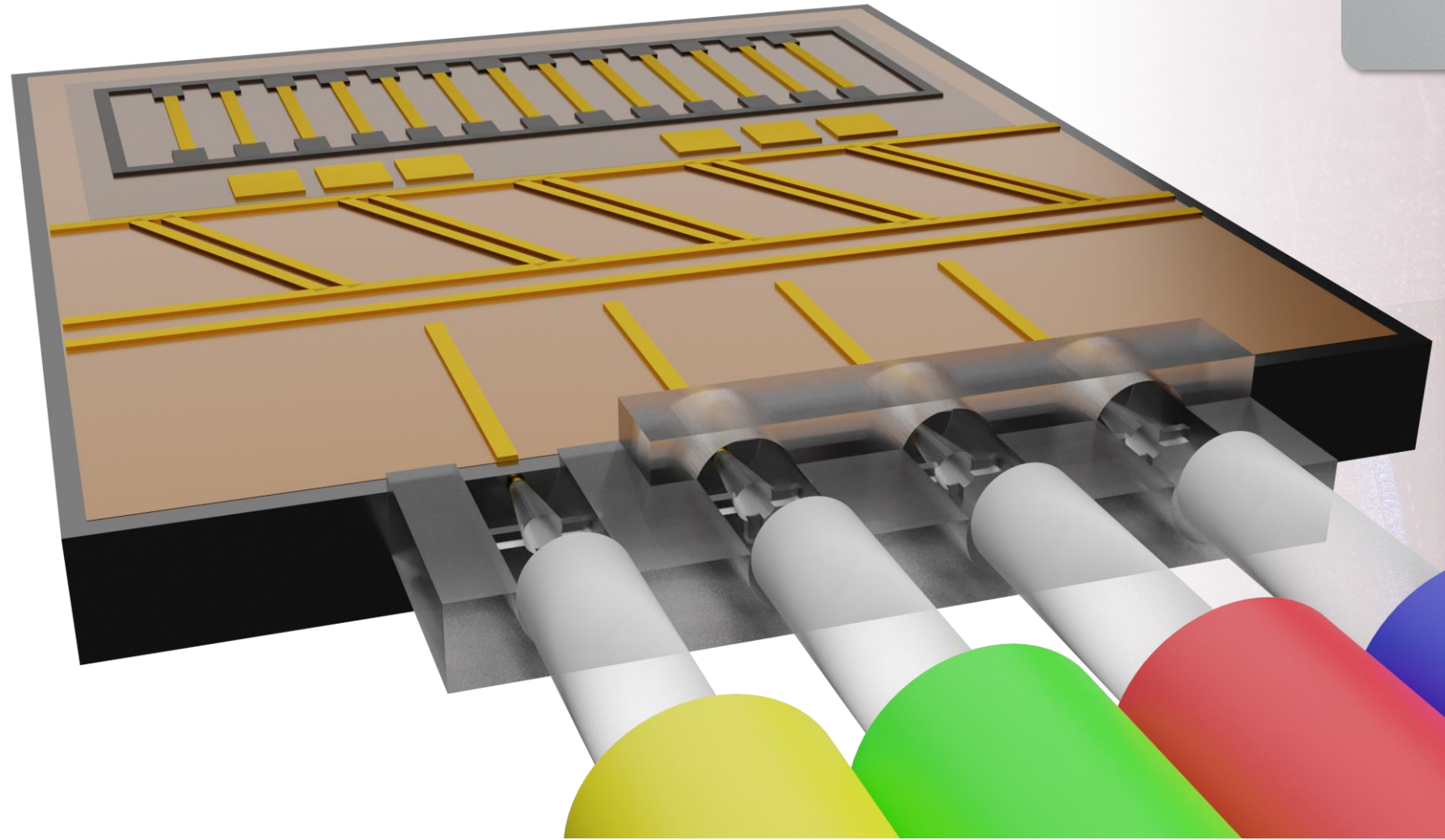
from NRE to low cost per module in volume ... to get high performance

ICON Photonics Technology



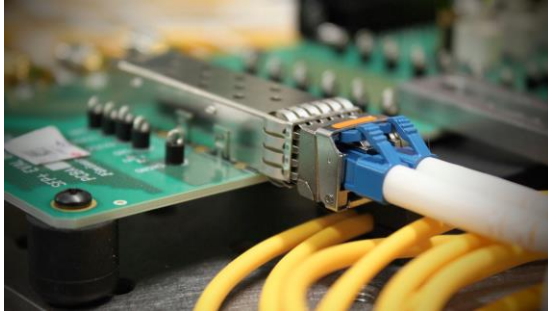
Guide each photon / Shape the beam / Compensate for misalignments

Focus on PIC to fiber coupling

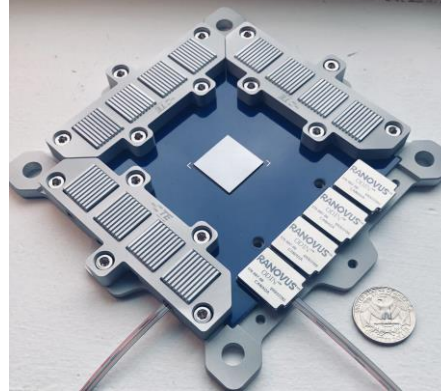


Market drivers

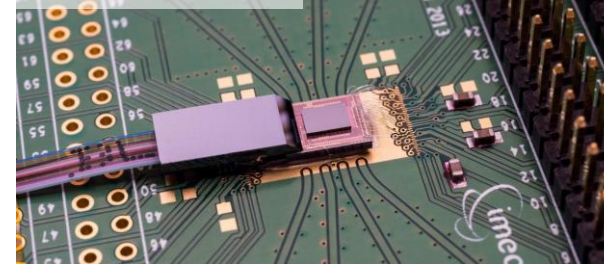
Pluggable Optics



Co-Packaged Optics (CPO)



CPO to 3D-chiplet



IMEC Si-PIC platform

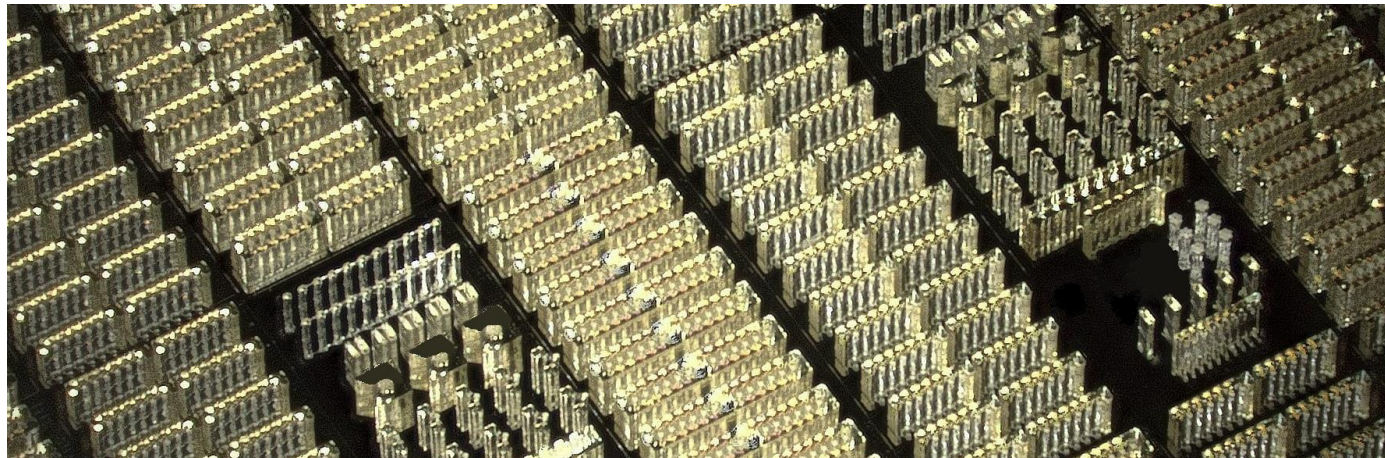
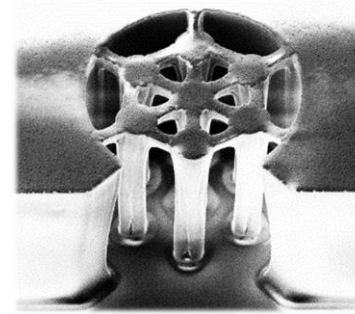
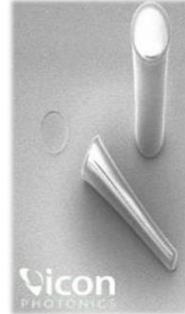
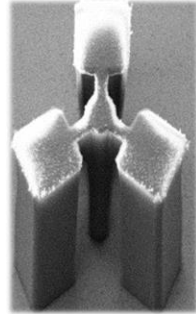
Ranovus 2021, nx100Gbps PAM4

- **Integration:** key to lower cost and higher density
- **Speed:** get smaller to get higher data rates
 - + Scalable and Cost-efficient model: <100\$ per 100Gbit/s
- **Robustness and attachability**
- **Efficiency:** save energy and save photons
 - + Going above the 98% efficiency
- Getting light In and Out of the chip **with standards at wafer-level**

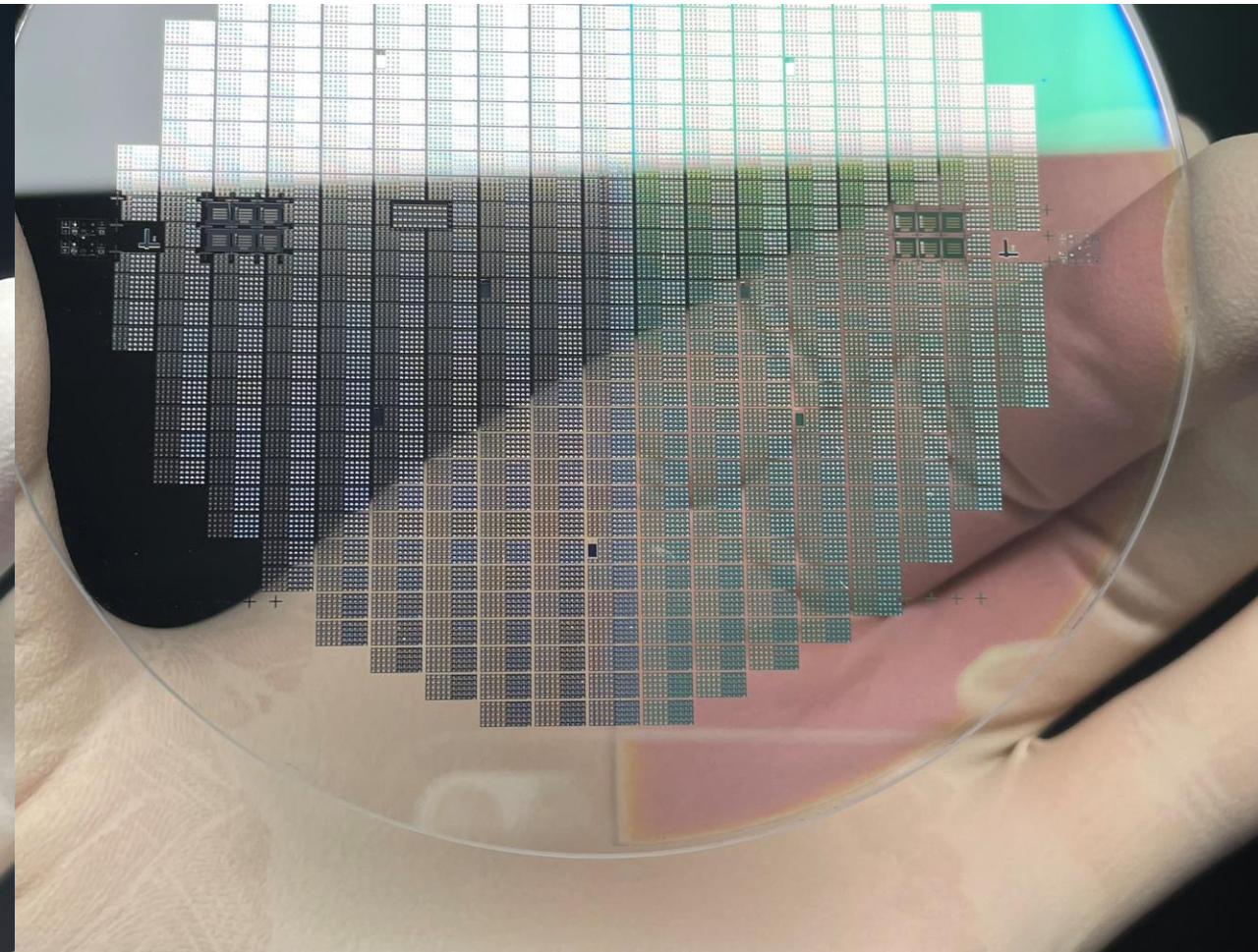
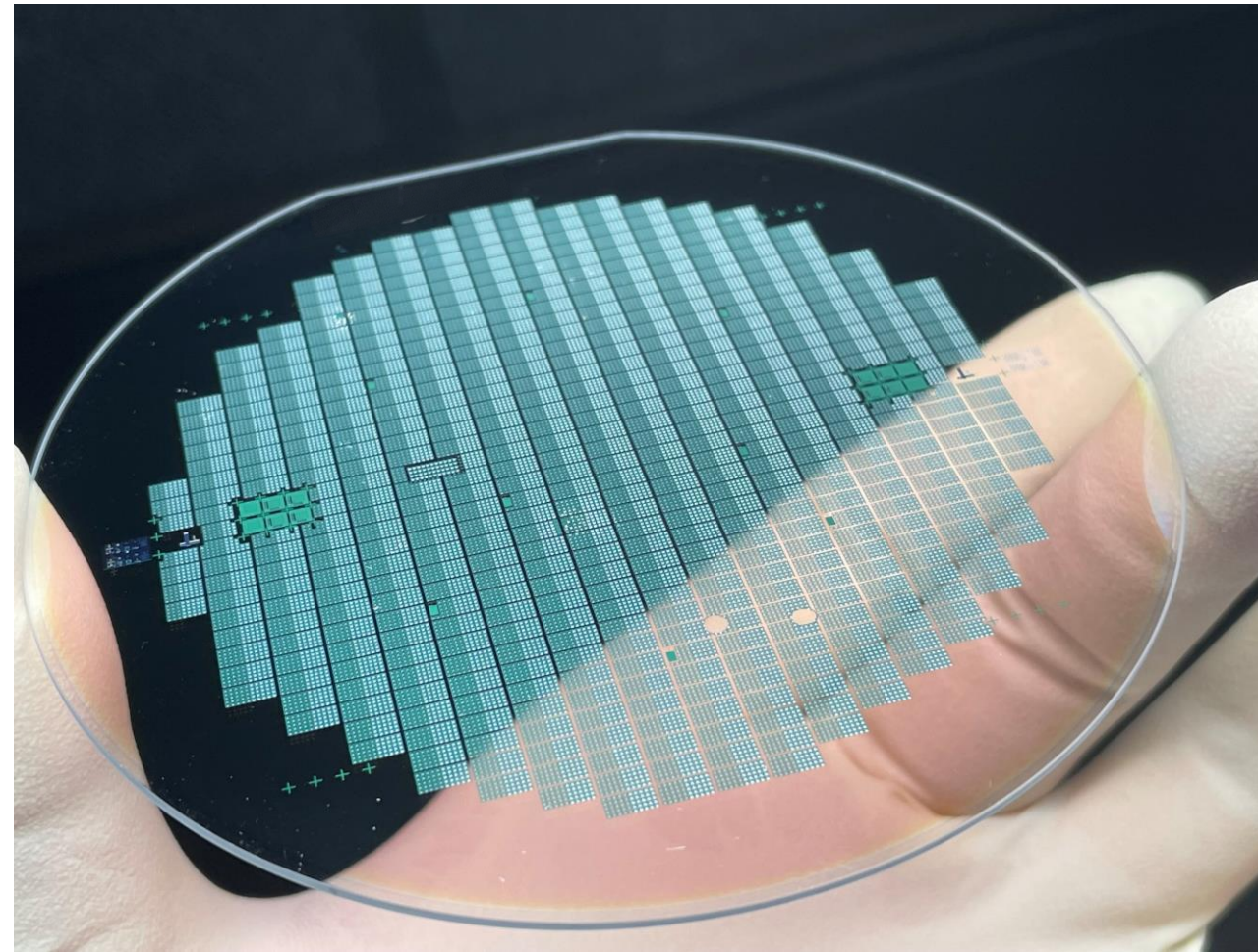
WAFER PRODUCTION

Some illustrations

Flexibility of shapes



Thousands of SSC per wafer with ARC



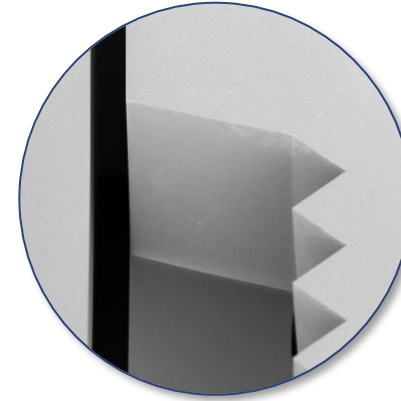
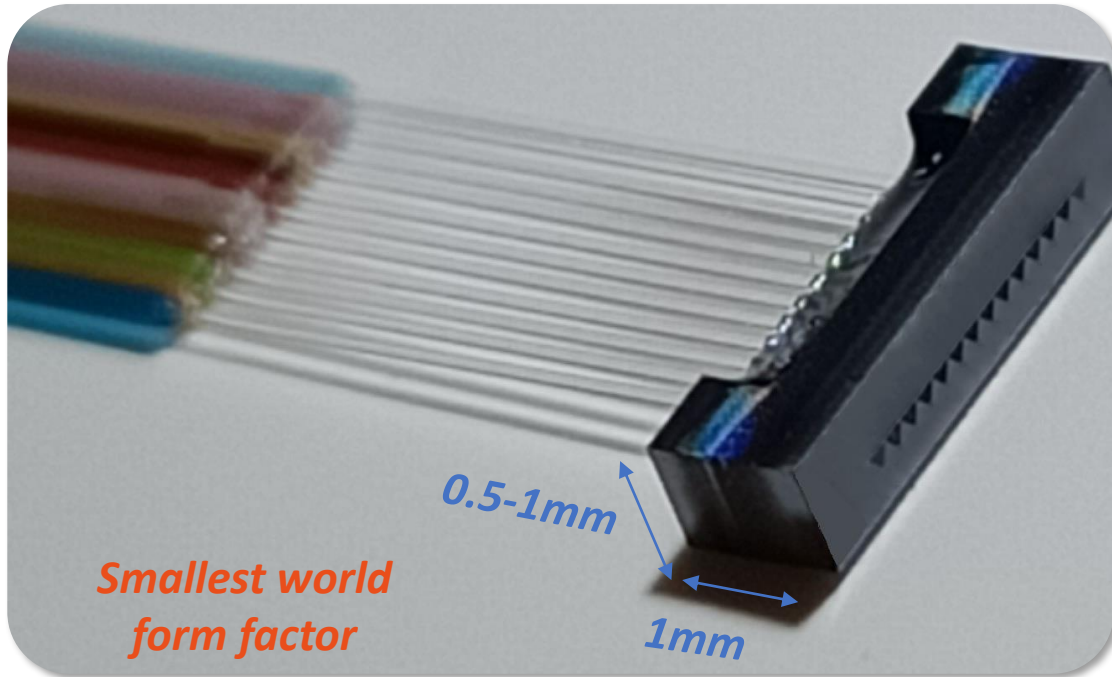
KEY BLOCKS FOR THE OPTICAL COUPLING

- ① Fiber maintaining and fixing to the PIC

Fiber maintaining

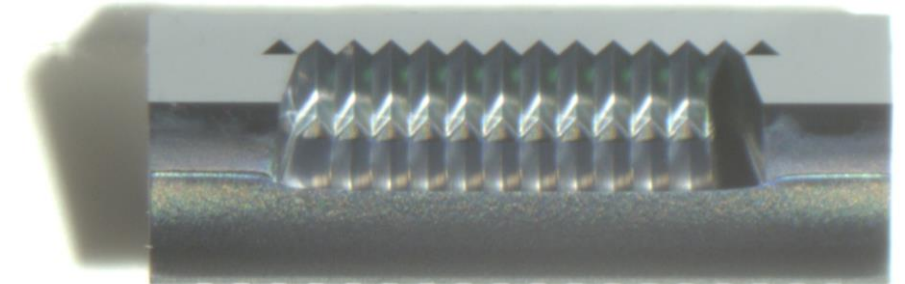
- *from standard V-grooves*

to advanced V-groove



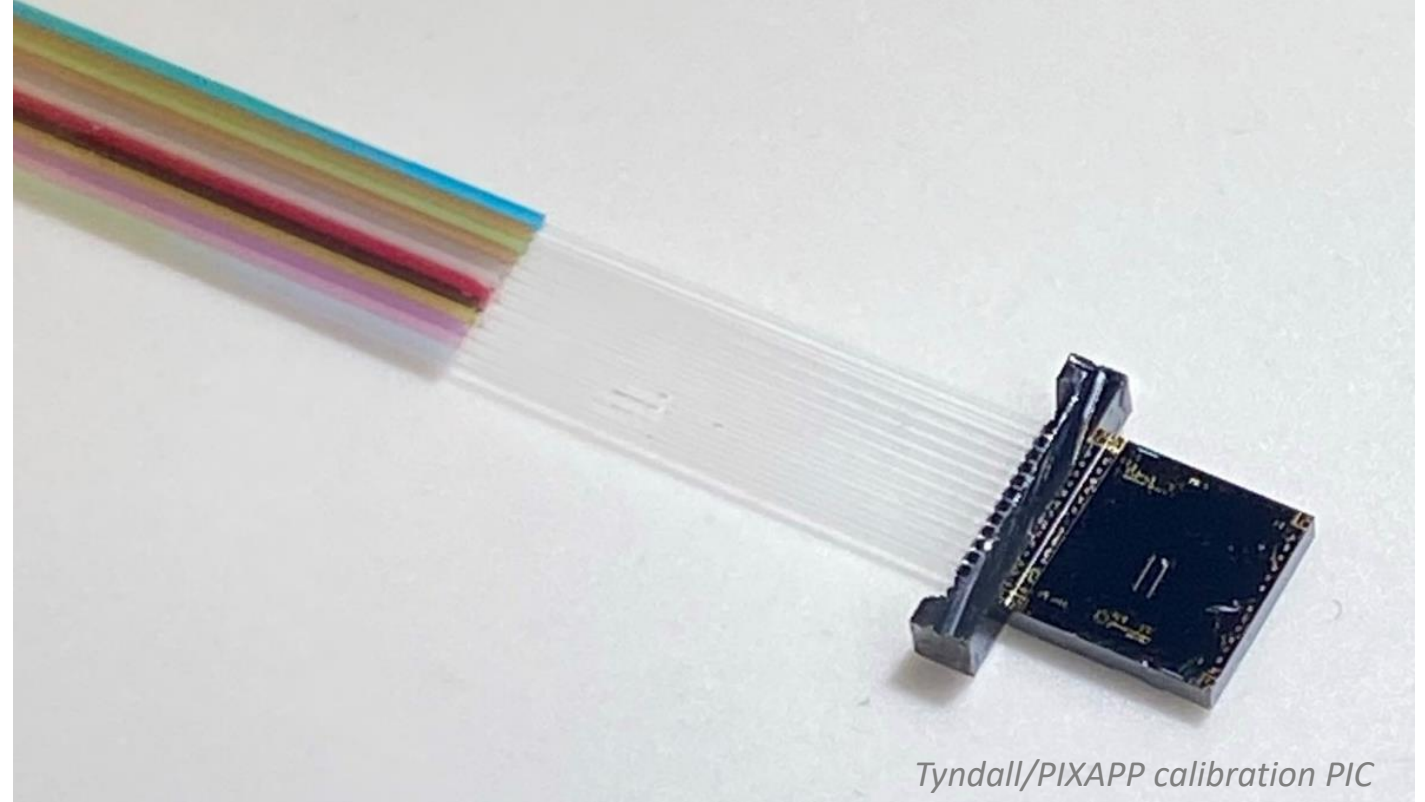
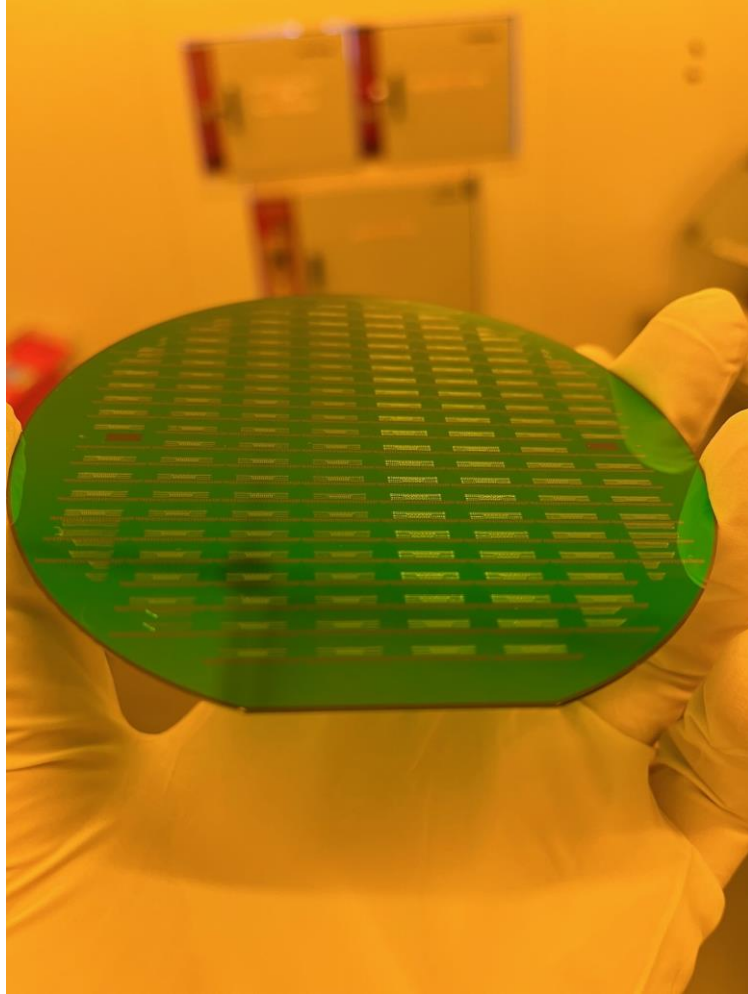
*fiber centering $<0.5\mu\text{m}$
from channel 1 to ... 128*

Patent pending



- ➔ Ultra compact V-grooves with integrated lid
- ➔ Pitch from 50 to 500 μm (82 μm – 127 μm – 250 μm)
- ➔ Arrays or matrices, regular or irregular shapes

MADE AT WAFER LEVEL

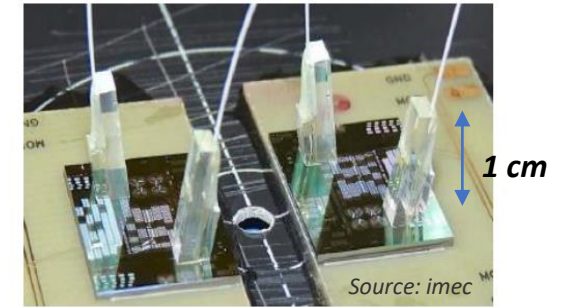
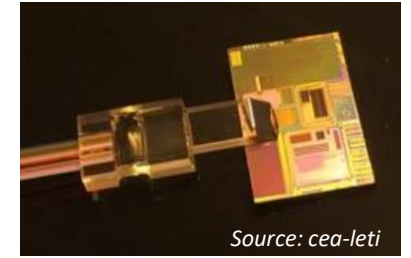
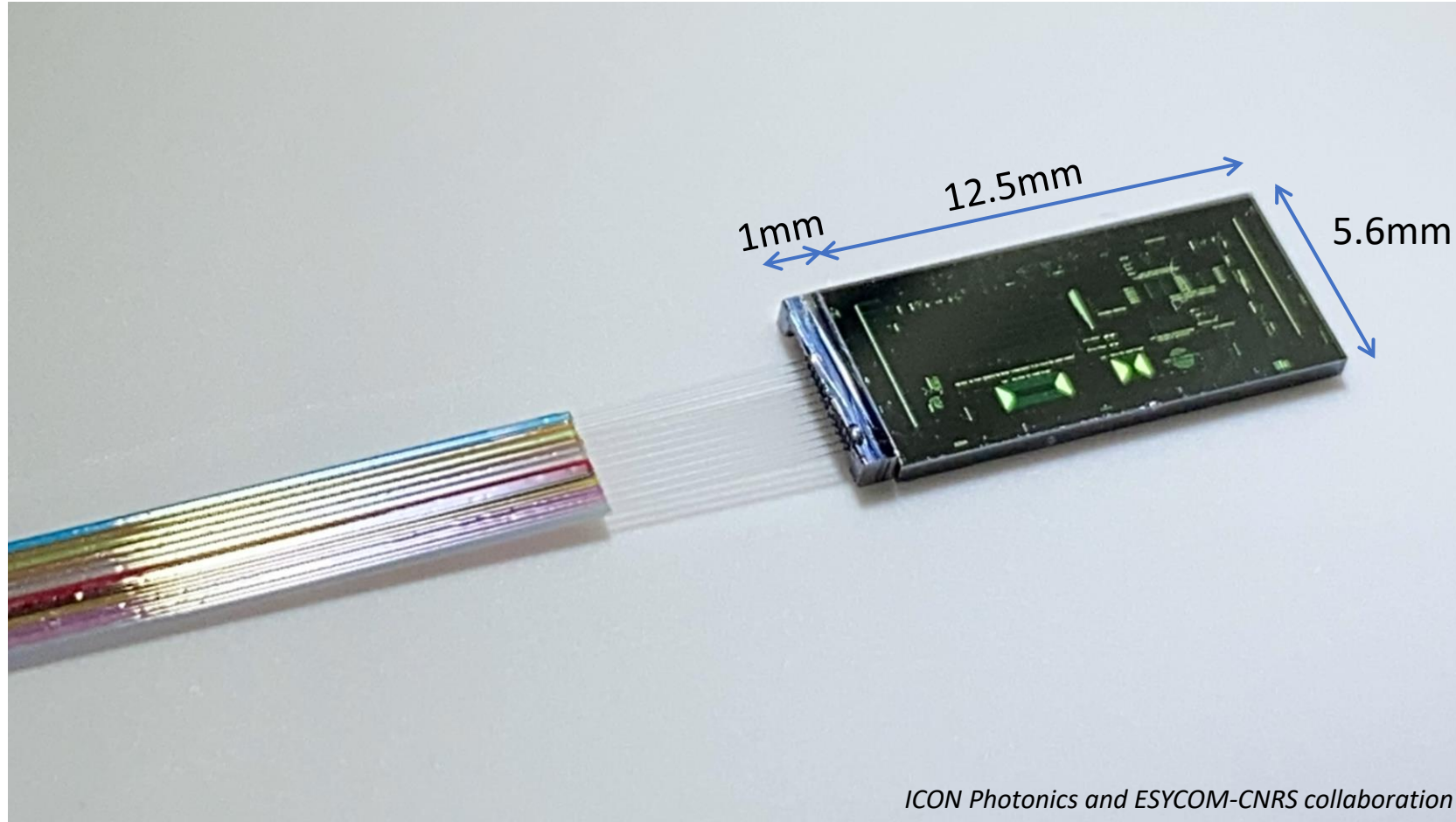


Tyndall/PIXAPP calibration PIC

SMALLEST FORM FACTOR Advanced V-GROOVE

How to showcase further?

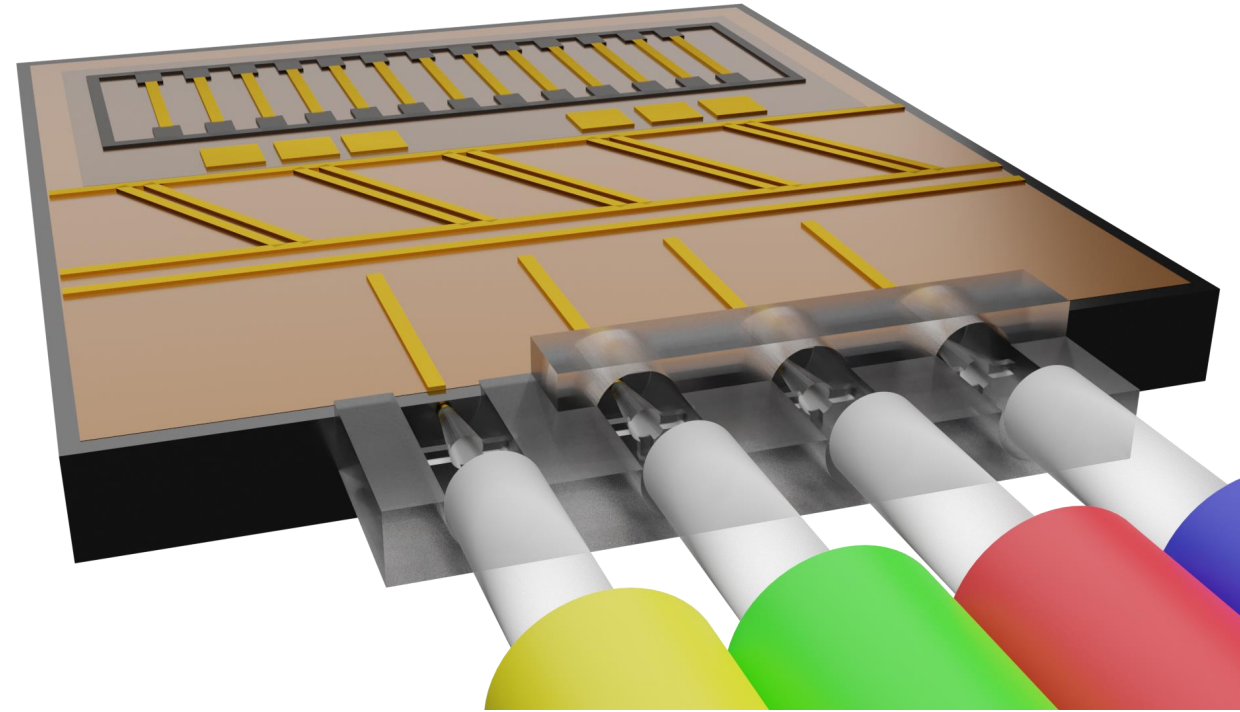
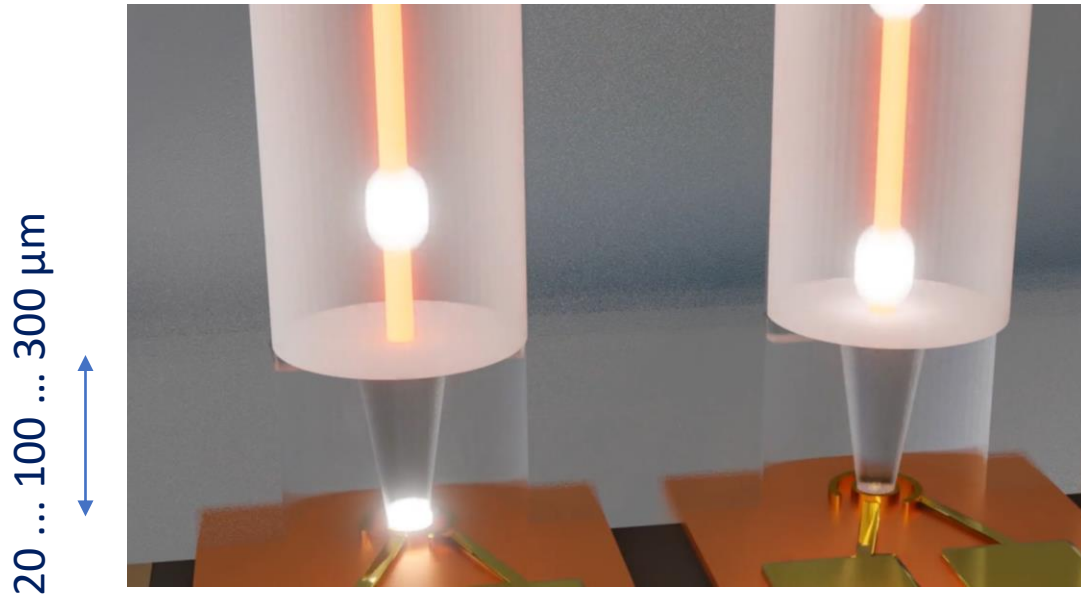
Ultra-compact FAU to PIC butt-coupling



KEY BLOCKS FOR THE OPTICAL COUPLING

② Spot-Size-Converters (SSC)

High contrast index tapers for SSC



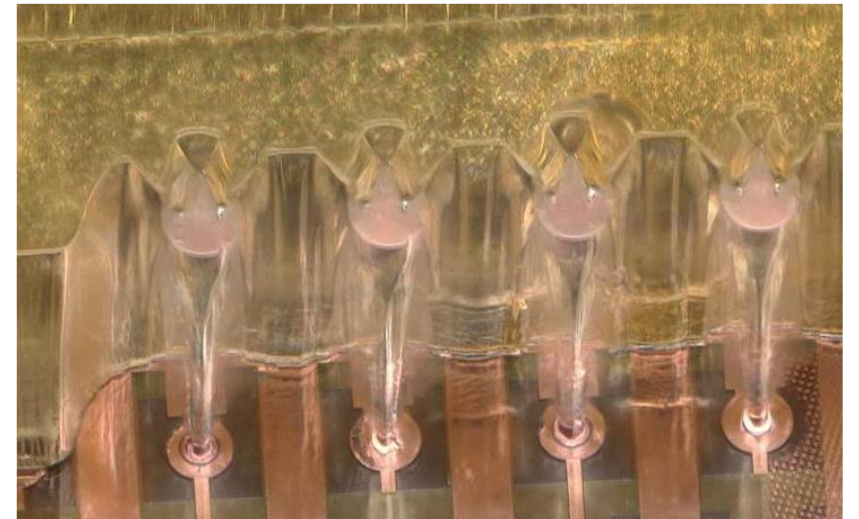
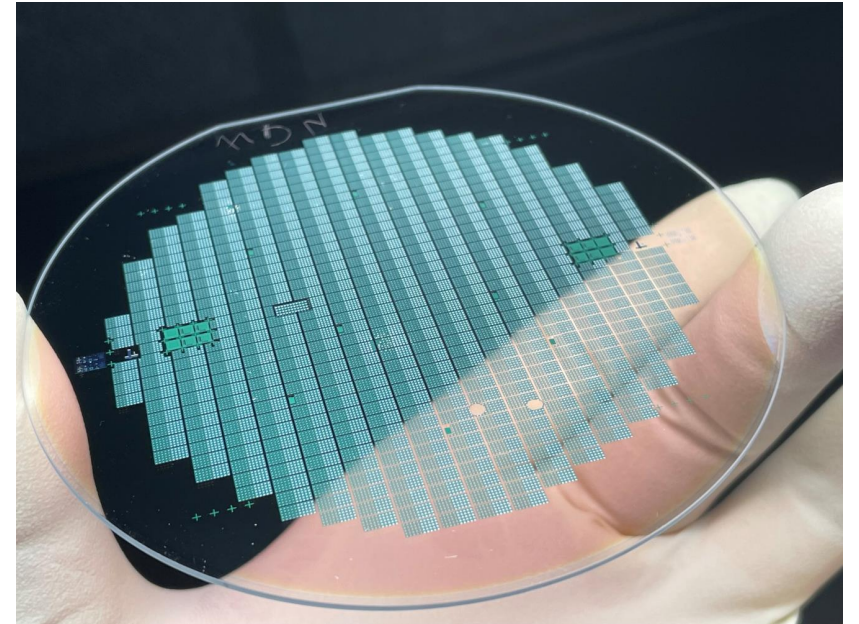
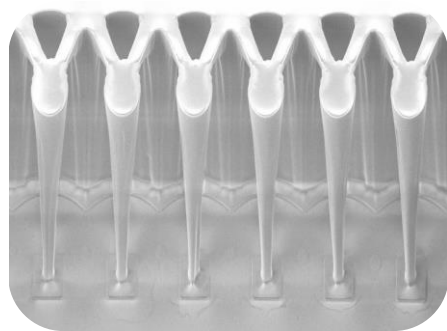
**Collect all photons / Shape the beam / Compensate for misalignments
with custom shapes and multi-layer design**

SSC / Beamshapers

Match
the MFD

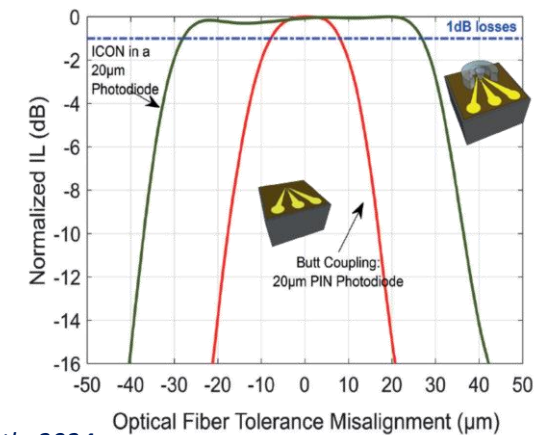
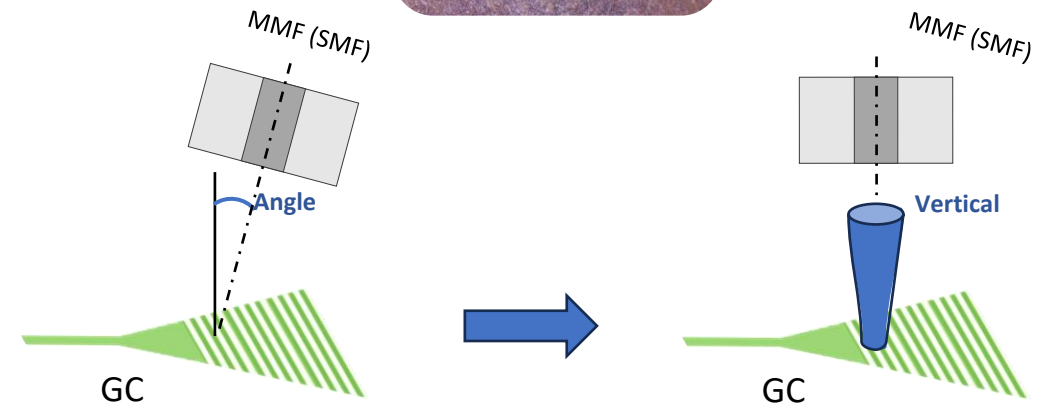
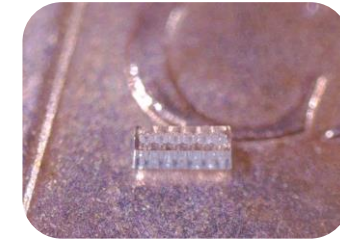
Increase
tolerances

- from 9-10 μm MFD fiber mode
to rectangular mode-shape 1x3 μm MFD
- Increase fiber alignment tolerance
*from 0.5 μm /0.5dB to 2 μm and more /0.5dB
(20 μm MMF)*



Functions of SSC / beamshapers

- Edge coupling of PIC & EEL
- Surface coupling with GC-PIC (MMF)
- Surface coupling of detectors / VCSELs




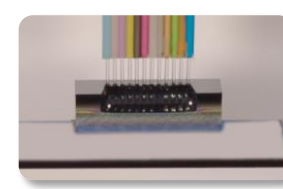
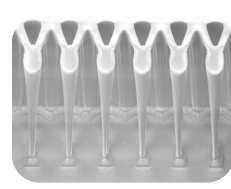












RESULTING COUPLING LOSSES

Coupling losses

from cryo to 105°C through TELCORDIA

T(%)	A(dB)	Gom(dB)
1%	-20	-40
10%	-10	-20
50%	-3.0	-6
63%	-2	-4
70%	-1.5	-3
80%	-1.0	-2
90%	-0.5	-1
93%	-0.3	-0.6
95%	-0.2	-0.4
98%	-0.1	-0.2
100%	0	0

Standard IL
Ultra-low IL

FAU MFD 9-10 μ m	SURFACE COUPLING (SMF / MMF)	FAU-SSC MFD 3 μ m
		
		
		
		
		
TELCORDIA	Cryo to >105°C	Cryo to >105°C

Upcoming MPW

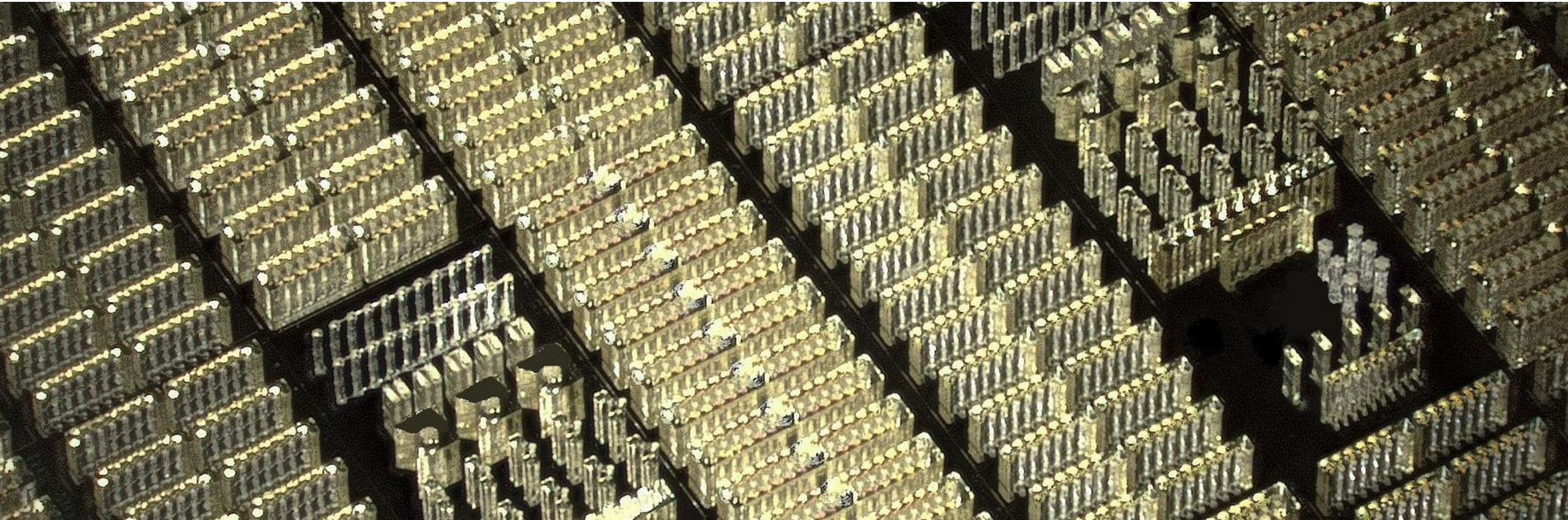


ARE WE USING
GREYSCALE / NIL / 2PP ?

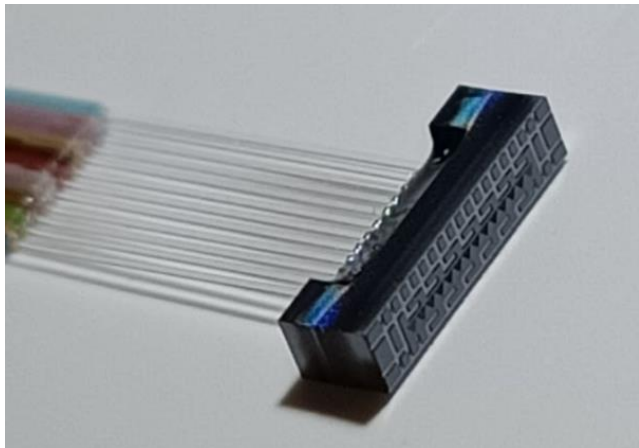
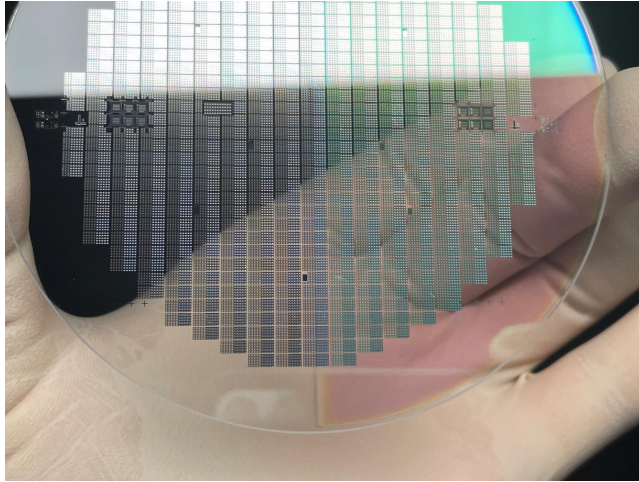
UV “standard” lithography

- Volume capabilities and low cost
- Not real 3D but 2.5D with layer stacking options
- Smooth surface due to wet chemistry
- Smart combination of wafer bonding / DRIE / photolitho
... combining various scales from μm to mm with high precision

Density of SSC on wafer



Announcement: Next MPW Run for FAU-SSC



Registration
July 2024

Tape-out septembre 2024
Delivery December 2024



Custom geometry, pitch (50 μ m to 500 μ m), number of fiber (1 to 128), ARC (940nm, 1550nm), fiber type (λ from 0.5 μ m-5 μ m), Elliptical shapes, PIC bonding service included



Share specifications: taper slope

- MMF : MFD ~20 μ m to 15 μ m
- SMF : MFD ~5 μ m to 3 μ m



Thanks!

jean-luc.polleux@icon-photonics.com

www.icon-photonics.com

